

	Hits	Search Text	DBs
29	64	((resist or photoresist or photosensitive) same develop\$4 same (expos\$4 or illuminat\$4 or irradiat\$4)) and ((surface\$4active or surfactant or (defect\$5 near12 preven\$5 near12 agent) or (surface near16 (modifying or modification or active))) same (vary\$4 or var\$5 or adjust\$4 or chang\$4 or alter\$4) same (amount or concentration or percentage or percent) same (resist or photoresist) same thickness)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
30	26	((resist or photoresist or photosensitive) same develop\$4 same (expos\$4 or illuminat\$4 or irradiat\$4)) and ((surface\$4active or surfactant or (defect\$5 near12 preven\$5 near12 agent) or (surface near16 (modifying or modification or active))) same (vary\$4 or var\$5 or adjust\$4 or chang\$4 or alter\$4) same (amount or concentration or percentage or percent) same (resist or photoresist) same thickness)	US-PGPUB

	Hits	Search Text	DBs
31	3	((resist or photoresist or photosensitive) same develop\$4 same (expos\$4 or illuminat\$4 or irradiat\$4)) and (((surface\$4active or (interfacial near5 active near5 agent) or surfactant or (defect\$5 near12 preven\$5 near12 agent) or (surface near16 (modifying or modification or active))) near6 (layer or film or coat\$4)) same (vary\$4 or var\$5 or adjust\$4 or chang\$4 or alter\$4) same (amount or concentration or percentage or percent) same (resist or photoresist) same thickness)	US-PGPUB
32	20	((resist or photoresist or photosensitive) same develop\$4 same (expos\$4 or illuminat\$4 or irradiat\$4)) and (((surface\$4active or (interfacial near5 active near5 agent) or surfactant or (defect\$5 near12 preven\$5 near12 agent) or (surface near16 (modifying or modification or active))) near6 (layer or film or coat\$4)) same (varying or varied or variable or adjust\$4 or chang\$4 or alter\$4) same (amount or concentration or percentage or percent) same (resist or photoresist) same thickness)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
33	7	((resist or photoresist or photosensitive) same develop\$4 same (expos\$4 or illuminat\$4 or irradiat\$4)) and (((surface\$4active or (interfacial near5 active near5 agent) or surfactant or (defect\$5 near12 preven\$5 near12 agent) or (surface near16 (modifying or modification or active))) near6 (layer or film or coat\$4)) same (determin\$5 or calculat\$4 or verifying) same (amount or concentration or percentage or percent) same (resist or photoresist) same thickness)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB
34	1	((resist or photoresist or photosensitive) same develop\$4 same (expos\$4 or illuminat\$4 or irradiat\$4)) and (((surface\$4active or (interfacial near5 active near5 agent) or surfactant or (defect\$5 near12 preven\$5 near12 agent) or (surface near16 (modifying or modification or active))) near6 (layer or film or coat\$4)) same (determin\$5 or calculat\$4 or verifying) same (amount or concentration or percentage or percent) same (resist or photoresist) same thickness)	US-PGPUB

	Hits	Search Text	DBs
35	64	((resist or photoresist or photosensitive) same develop\$4 same (expos\$4 or illuminat\$4 or irradiat\$4)) and ((surface\$4active or surfactant or (defect\$5 near12 preven\$5 near12 agent) or (surface near16 (modifying or modification or active))) same (vary\$4 or var\$5 or adjust\$4 or chang\$4 or alter\$4) same (amount or concentration or percentage or percent) same (resist or photoresist) same thickness)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
36	26	((resist or photoresist or photosensitive) same develop\$4 same (expos\$4 or illuminat\$4 or irradiat\$4)) and ((surface\$4active or surfactant or (defect\$5 near12 preven\$5 near12 agent) or (surface near16 (modifying or modification or active))) same (vary\$4 or var\$5 or adjust\$4 or chang\$4 or alter\$4) same (amount or concentration or percentage or percent) same (resist or photoresist) same thickness)	US-PGPUB
37	38	S43 NOT S44	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
38	1	134/24.ccls. and develop\$5 and (nozzle same (multiple or pluralit\$4) same (shape or geometr\$6) same (cylindrical or circular or circle or band or rectang\$4)) and (surface\$4active or (surface near9 (active or modifying or modification or alter\$4)) or surfactant or (defect near6 prevent\$4 near9 agent))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
39	6	396/627.ccls. and develop\$5 and (nozzle same (multiple or pluralit\$4) same (shape or geometr\$6) same (cylindrical or circular or circle or band or rectang\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
40	2	430/434.ccls. and develop\$5 and (nozzle same (multiple or pluralit\$4) same (shape or geometr\$6) same (cylindrical or circular or circle or band or rectang\$4)) and (surface\$4active or (surface near9 (active or modifying or modification or alter\$4)) or surfactant or (defect near6 prevent\$4 near9 agent)) and (resist or photoresist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
41	2	430/311.ccls. and develop\$5 and (nozzle same (multiple or pluralit\$4) same (shape or geometr\$6) same (cylindrical or circular or circle or band or rectang\$4)) and (surface\$4active or (surface near9 (active or modifying or modification or alter\$4)) or surfactant or (defect near6 prevent\$4 near9 agent)) and (resist or photoresist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
42	36	"430"/\$.ccls. and ((resist or photoresist or photosensitive) same develop\$4 same (expos\$4 or illuminat\$4 or irradiat\$4)) and ((surface\$4active or surfactant or (defect\$5 near12 preven\$5 near12 agent) or (surface near16 (modifying or modification or active))) same (vary\$4 or var\$5 or adjust\$4 or chang\$4 or alter\$4) same (amount or concentration or percentage or percent) same (resist or photoresist) same thickness)	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
43	36	"430"/\$.ccls. and ((resist or photoresist or photosensitive) same develop\$4 same (expos\$4 or illuminat\$4 or irradiat\$4)) and ((surface\$4active or surfactant or (defect\$5 near12 preven\$5 near12 agent) or (surface near16 (modifying or modification or active))) same (vary\$4 or var\$5 or adjust\$4 or chang\$4 or alter\$4) same (amount or concentration or percentage or percent) same (resist or photoresist) same thickness)	US-PGPUB; USPAT

	Hits	Search Text	DBs
44	0	"134"/\$.ccls. and ((resist or photoresist or photosensitive) same develop\$4 same (expos\$4 or illuminat\$4 or irradiat\$4)) and ((surface\$4active or surfactant or (defect\$5 near12 preven\$5 near12 agent) or (surface near16 (modifying or modification or active))) same (vary\$4 or var\$5 or adjust\$4 or chang\$4 or alter\$4) same (amount or concentration or percentage or percent) same (resist or photoresist) same thickness)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
45	0	"396"/\$.ccls. and ((resist or photoresist or photosensitive) same develop\$4 same (expos\$4 or illuminat\$4 or irradiat\$4)) and ((surface\$4active or surfactant or (defect\$5 near12 preven\$5 near12 agent) or (surface near16 (modifying or modification or active))) same (vary\$4 or var\$5 or adjust\$4 or chang\$4 or alter\$4) same (amount or concentration or percentage or percent) same (resist or photoresist) same thickness)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB